

3600.2406
January 23, 2003 (1:44pm)

Docket: AM-2406

REMARKS

Claims 21-44 remain in the application.

Claim 21 has been amended to more definitely specify a target of magnetic material.

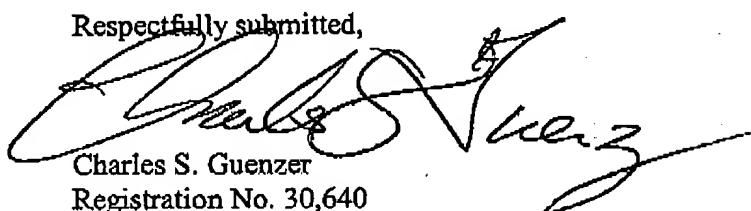
A new set of claims 41-44 has been added.

The rejections contained in the Office Action dated August 27, 2002 are traversed for the reasons presented in the Response filed October 25, 2002. The Request for Continued Examination requested entry of the amendments filed on October 25, 2002 and also cited new art.

In view of the above amendments and remarks, reconsideration and allowance of all claims are respectfully requested. If the Examiner believes that a telephone interview would be helpful, he is invited to contact the undersigned attorney at the listed telephone number, which is on California time.

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Respectfully submitted,


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Version with markings to show changes made

21. (Amended) An apparatus for depositing a magnetic film, comprising:
a sputtering chamber containing a target comprising a magnetic sputtering material, a substrate support having a substrate surface that is separated from the target, and a grounded collimator positioned between the target and the substrate support; and
an annular magnet array disposed within the sputtering chamber, the annular magnet array being configured to form a magnetic field that is substantially parallel to the substrate surface of the substrate support, the annular magnet array being concentrically positioned around an outer perimeter of the substrate surface of the substrate support.

41. (New) An apparatus for depositing a magnetic film, comprising:
a sputtering chamber configured to receive a sputtering target for sputter depositing a magnetically alignable material onto a substrate supported on a support surface in opposition to said target along an axial direction; and
a stationary annular array of permanent magnets surrounding an outer periphery of said support surface and continuously extending from one side to the other side of said support surface parallel to said central axis and creating a magnetic field extending horizontally along said support surface.

42. (New) The apparatus of claim 41, wherein said array is a Halbach array.

43. (New) The apparatus of claim 40, further comprising a grounded collimator positioned between said target and said support surface.

44. (New) The apparatus of claim 40, wherein said material comprises nickel and iron.